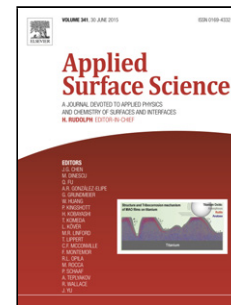


Accepted Manuscript

Title: Correlation between oxidant concentrations, morphological aspects and etching kinetics of silicon nanowires during silver-assist electroless etching

Authors: Bisma Moumni, Abdelkader Ben Jaballah



PII: S0169-4332(17)31765-8
DOI: <http://dx.doi.org/doi:10.1016/j.apsusc.2017.06.110>
Reference: APSUSC 36310

To appear in: *APSUSC*

Received date: 31-3-2017
Revised date: 5-6-2017
Accepted date: 8-6-2017

Please cite this article as: Bisma Moumni, Abdelkader Ben Jaballah, Correlation between oxidant concentrations, morphological aspects and etching kinetics of silicon nanowires during silver-assist electroless etching, *Applied Surface Science* <http://dx.doi.org/10.1016/j.apsusc.2017.06.110>

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

Correlation between oxidant concentrations, morphological aspects and etching kinetics of silicon nanowires during silver-assist electroless etching

Besma Moumni¹, Abdelkader Ben Jaballah^{*,1,2}

¹ Photovoltaic Laboratory, Research and Technology Centre of Energy (CRTEn), Borj Cedria Technopark, PB 95 Hammam Lif 2050, Tunisia.

² Department of Physics, Faculty of Science and Arts in Samtha, Jazan University, Jazan-Kingdom of Saudi Arabia.

***Corresponding author: e-mail: gadour2003@yahoo.fr,**

Download English Version:

<https://daneshyari.com/en/article/5347311>

Download Persian Version:

<https://daneshyari.com/article/5347311>

[Daneshyari.com](https://daneshyari.com)